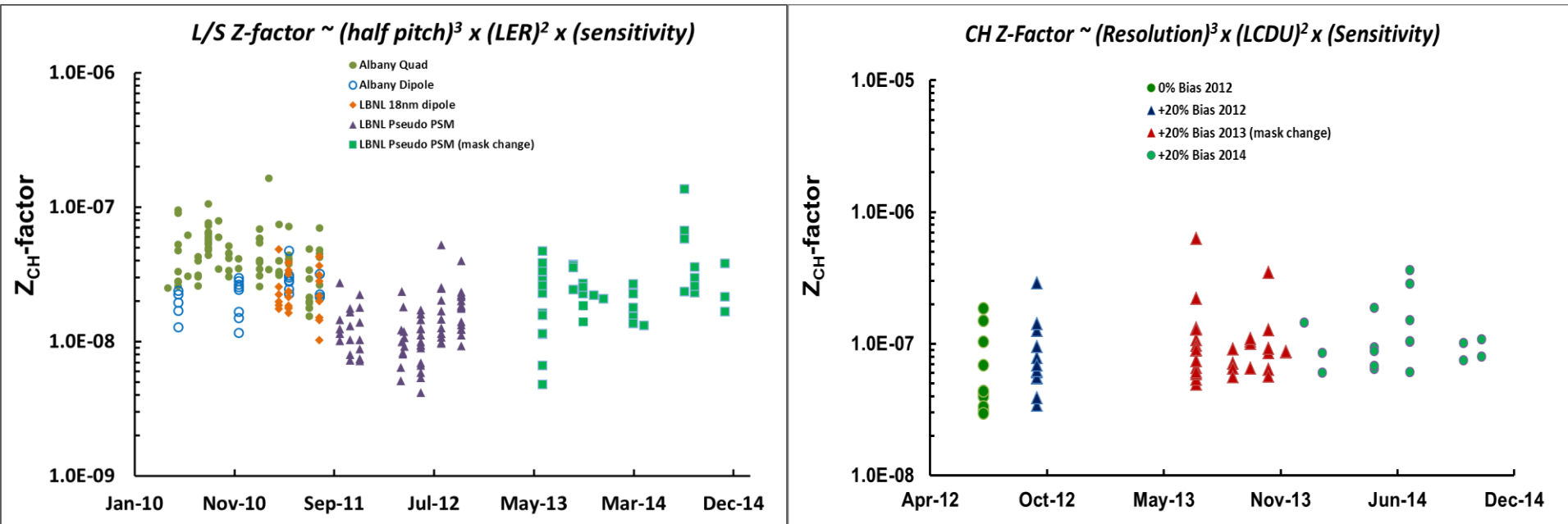


Public Meeting Notice

- Welcome to the IEUVI Resist TWG meeting, please sign in
- This meeting is classified as an “Open Conference” per the U.S. Export Administration Regulations.
- Confidential or Proprietary information may NOT be disclosed.
- All meeting attendees are permitted to take notes or otherwise make a personal record of these proceedings.
- Presentations will be available to the public including posting on the SEMATECH/IEUVI website.

Resist Imaging Performance Tracking



*Z-factor $\sim (\text{half pitch})^3 \cdot (\text{LER}/\text{LCDU})^2 \cdot (\text{Sensitivity})$

- EUV resist development is expected to make progress from relaxation of outgas specification
- 2014 results haven't show improvement in RLS tradeoff
- Some of novel resist materials have shown promising results in 2014

Action Items from last TWG meeting

- Continue the round robin test and reduce site-to-site variables
- Continue and extend the family test to multiple resist suppliers
- Continue EUV resist development towards HVM

Resist TWG Agenda



Time	Title	Presenter
1:00 PM – 1:10 PM	Welcome and Introductions	<i>Y. Fan, SEMATECH</i>
1:10 PM – 1:40 PM	ASML update	<i>N. Harned, ASML</i>
1:40 PM – 2:00 PM	EIDEC outgas testing update	<i>E. Shiobara, EIDEC</i>
2:00 PM – 2:10 PM	IMEC outgas testing update	<i>R. Gronheid, IMEC</i>
2:10 PM – 2:20 PM	NIST outgas testing update	<i>B. Berg & S. Hill, NIST</i>
2:20 PM – 2:30 PM	SEMATECH outgas testing update	<i>Y. Fan, SEMATECH</i>
2:30 PM – 2:50 PM	Outgassing round table discussion	<i>ASML & SEMATECH</i>
2:50 PM – 3:10 PM	Break	
3:10 PM – 3:30 PM	Dry development rinse process and material for EUV	<i>W. Shibayama, Nissan Chemical</i>
3:30 PM – 3:50 PM	Process enhancement of EUV materials	<i>S. Tarutani, EMD/Merck/AZ</i>
3:50 PM – 4:10 PM	Understanding electron energy loss mechanisms in EUV resists using EELS and first-principles calculations	<i>R. Bartynski, Rutgers University</i>
4:10 PM – 4:30 PM	PAG cross sections measurements of low energy electrons	<i>G. Denbeaux, CNSE SUNY PI</i>
4:30 PM – 4:40 PM	Summary	<i>Y. Fan, SEMATECH</i>